ICJO

MEMS/MOEMS FOUNDRY SERVICES

From Design to Complete Instrument Development

INO offers a complete range of MEMS/ MOEMS foundry services. Whether you need a very specific service or a fullyintegrated MEMS creation process, we have the resources, expertise, and flexibility to help you reach your goals and deliver results. Our state-of-the-art 4,630 sq. ft. clean-room facility is adapted to the processing of 6" and 8" substrates. Every year INO provides MEMS/MOEMS foundry services to 15 to 25 clients including universities, startups and large companies.

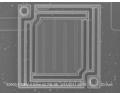
Expertise	Business Model and Offer		
 Simulations Surface micromachining with multiple sacrificial layers Integration of MEMS with CMOS electronics Hermetic packaging Heterogeneous assembly Optical design Electronics 	MEMS Manufacturing (50 wafers/year; 6 wafers/lot; 3-4 month cycle) • Simulations and design • Process flow development • Prototyping • Short-series manufacturing • Extensive testing	 MEMS Packaging (200 packages per month*) Device packaging using INO standard platforms New package design Process adaptation and development *1" square 68 LCC ceramic package 	 Other arrangements Technology transfers Joint R&D (product development) Joint ventures

Basic Building Blocks: Multi-Layer Suspended Platforms

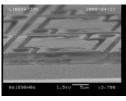
Single and double-level multi-layer platforms



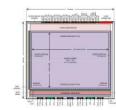
17 μm single-level platform

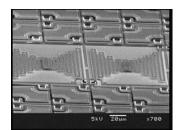


35 μm Single-level platform



25 μm double-level platform





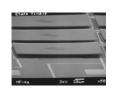
MEMS-CMOS IC INTEGRATION

- Support to design of mixed-signal CMOS ICs compatible with MEMS
- CMOS foundry selection
- Integration with CMOS circuits
- CMOS post-processing for MEMS (wafer coring)

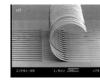
MEMS-Pirani Pressure Microsensors

- Sensing devices that can be co-integrated with MEMS devices in packages or on-chip
- Patented measurement technique embedded in control software
- Repeatability (typical): ±1.5% of reading from 3 mTorr to 760 Torr
- Accuracy (typical) ±2% from 10 mTorr-760Torr
- Accuracy (typical) ±5% from 3 mTorr-10 mTorr
- Calibration stability with temperature of the substrate < 0.7%/K
- Leak rates << conventional methods 10-16 Torr.L/sec

INO **MEMS/MOEMS FOUNDRY SERVICES**







Heterogeneous Assembly: Multichip Structures

Examples of Achievements: Micromirrors and Louvers





Large Deflection Angle Mirrors



SLM Mirrors

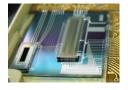
Flexure Hinge Mirrors Piston-like Micromirrors

Zipping Actuators

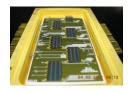




Inertial **Measurement Unit** (IMU) and its CMOS ROIC on a ceramic routing circuit



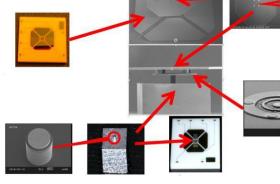
FPA and its CMOS **ROIC** on routing circuit (Si+ceramic)



Staggered assembly of 6 IRL 512x3 bolometricFPA's (alignment tolerance better than 50 µm)

Heterogeneous Assembly: Bulding Blocks

1. Substrate+ actuation electrodes (metallization patterning by lift-off)



4. Mirror

(fab: sputter deposition of reflective layer, electroplating, DRIE, dicing, release from wafer carrier: assembly: flip-chip bonding)

3. Gimbals spring (fab: electroplating; assembly: flip-chip bonding, release from wafer carrier)

2. Supporting post

(fab: electroplating, DRIE, dicing; assembly: flip-chip bonding)

Gen4 Package

KEY APPLICATIONS

- The ceramic LCC vacuum packaging technology was developed for uncooled bolometric detectors.
- The package can also accommodate other MEMS devices that require a vacuum environment ≤1 mTorr

ADVANTAGES

- · High productivity due to batch processing
- Low-cost
- Compact size
- Fluxless technology
- Compatible with temperature sensitive devices
- · Flexibility in package geometry, window materials and solder alloys
- Integrated pressure sensors for cavity pressure monitoring



Gen5 Package

KEY APPLICATIONS

 High-end military and space applications

ADVANTAGES

- Hermeticity yield > 90% (in progress)
- Internal pressure < 5 mTorr
- Refireable getters
- Targeted lifetime of 25 years
- Scalable platform
- Unique pumping and pinching capability offering external services outside of USA

